

Notice of References Cited	Application/Control No. 10/634,001	Applicant(s)/Patent Under Reexamination CHANG ET AL.	
	Examiner Patricia A. George	Art Unit 1765	Page 1 of 2

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	C	US-6,284,665	09-2001	Lill et al.	438/710
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NON-PATENT DOCUMENTS

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✓	U	The Handbook of Plasma Processing Technology - Fundamentals, Etching, Deposition, and Surface Interactions, edited by Rossnagel, page 198, 1990
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.